

**Efficient porous molybdenum diselenide catalyst for
electrochemical hydrogen generation**

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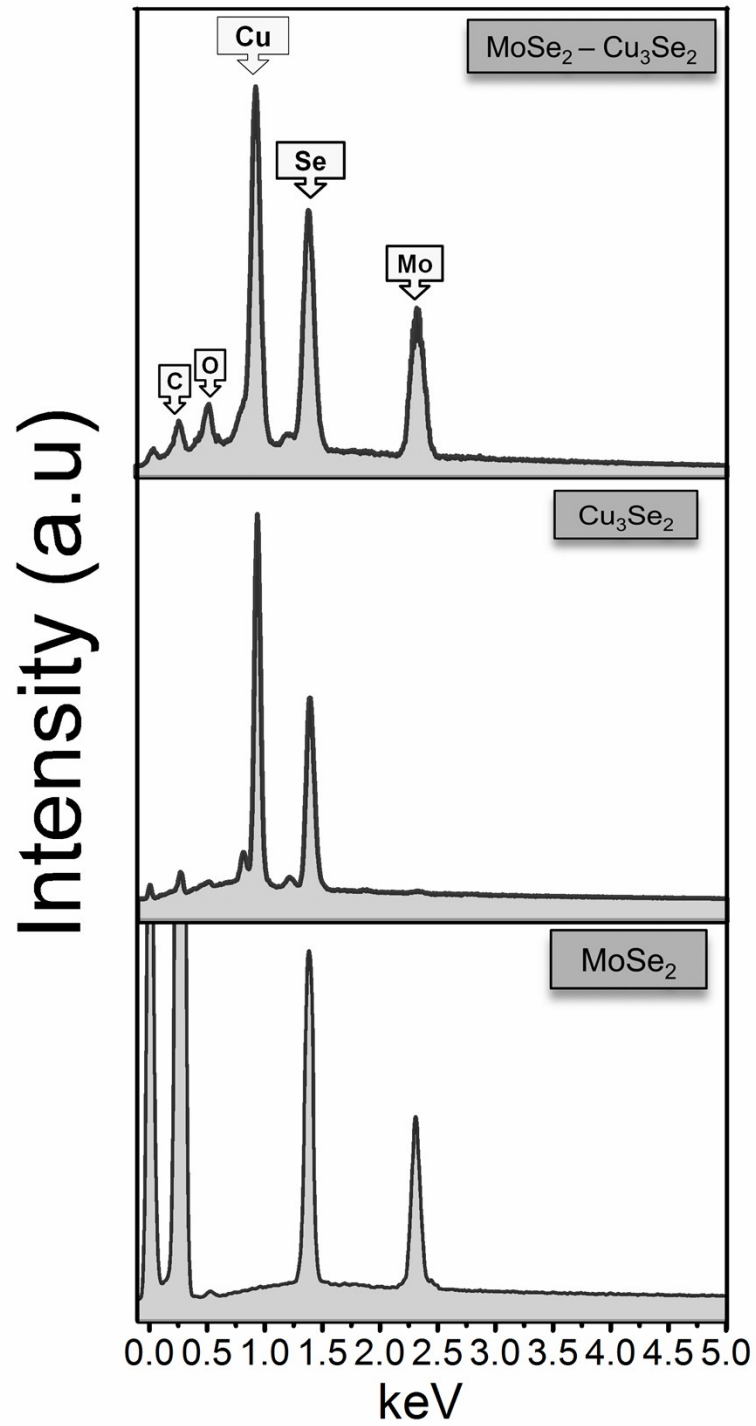


Figure S1 EDS spectrum of pure MoSe₂ film, pure Cu₃Se₂ film and composite Mo/Cu obtained from 2:2 volume ratio.

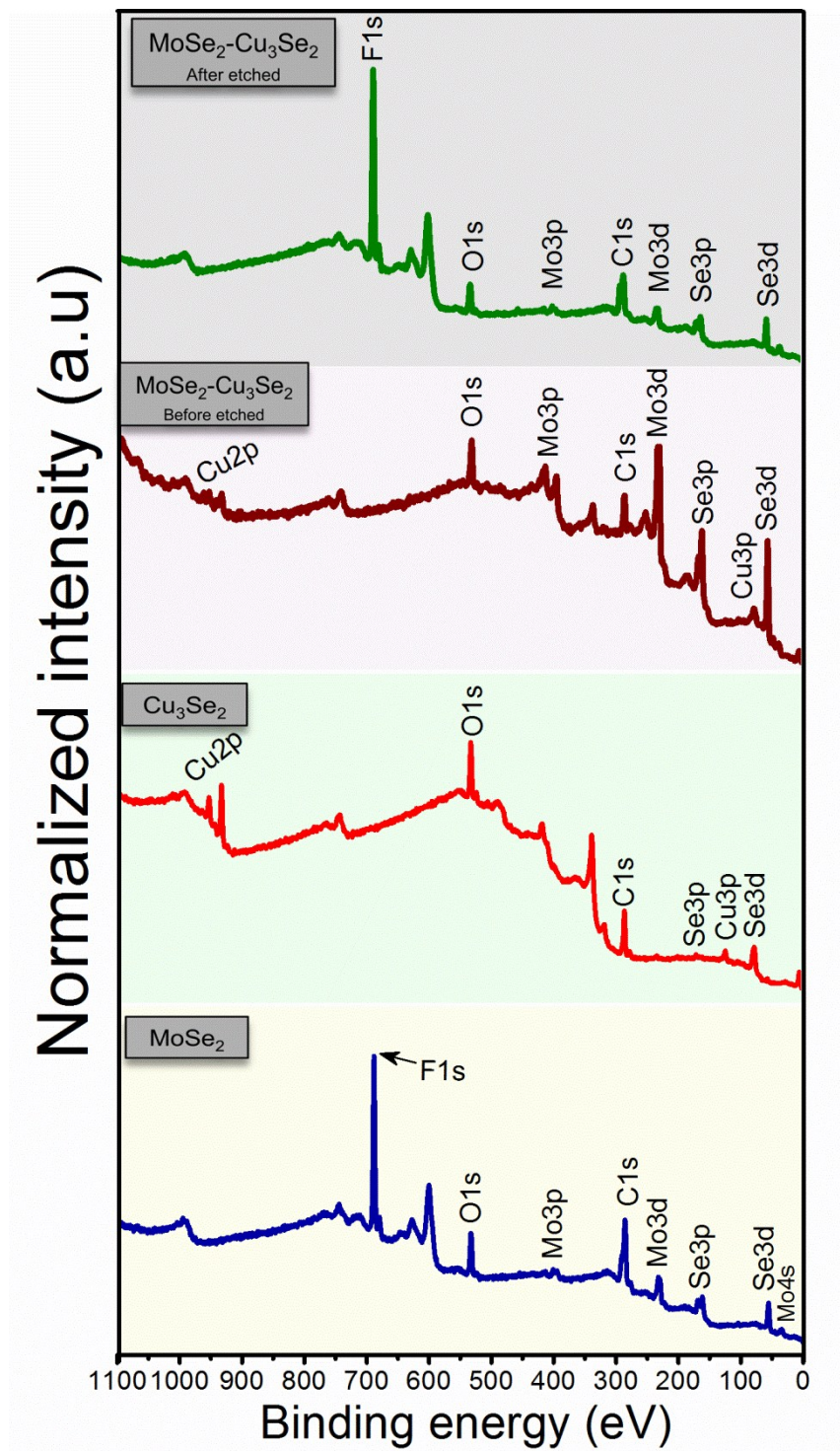


Figure S2 The survey XPS spectrum of Mo3d, Cu2p and Se3d obtained from pure MoSe₂ film, pure Cu₃Se₂ film and composite Mo/Cu obtained from 2:2 volume ratio before and after etched copper components out.

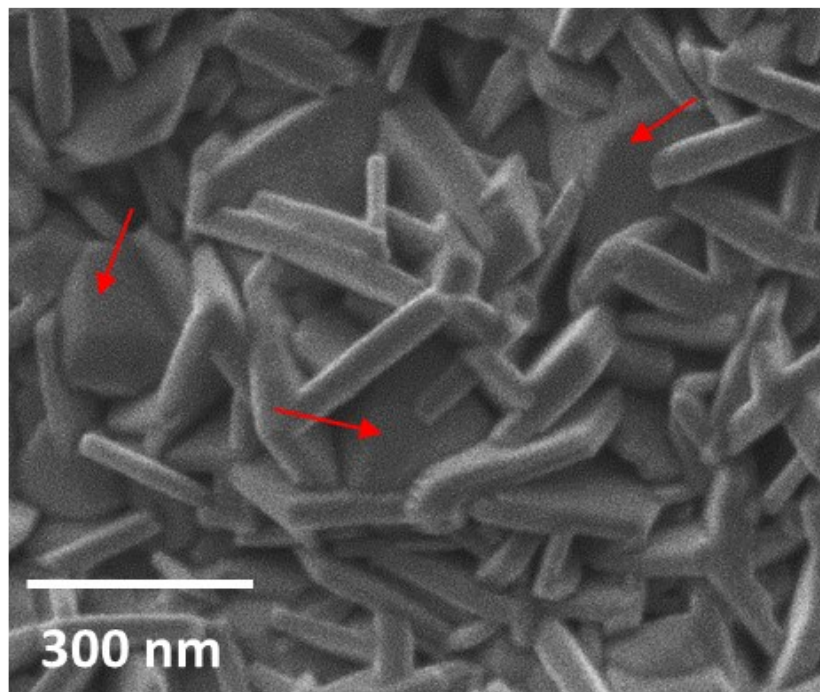


Figure S3 SEM images obtained from the volume ratio of 0.08 M Mo and 0.04 M Cu plating solution 4:1 before etching process, with applied potential at -0.6 V for 20 mC. The red arrows show the location of the copper before etching.

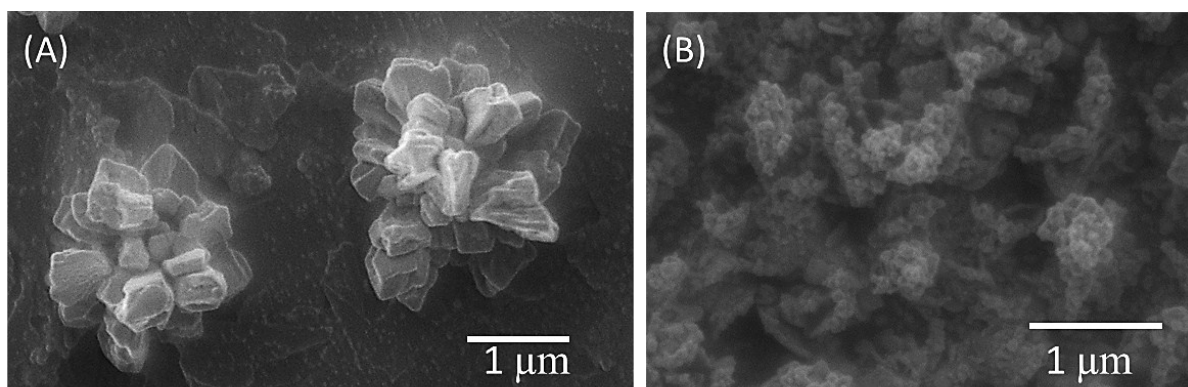


Figure S4 SEM images of 4:1 volume ratio of 0.08 M Mo: 0.04 M Cu at deposition potential (A) -0.4 V (B) -0.8 V for 20 mC.

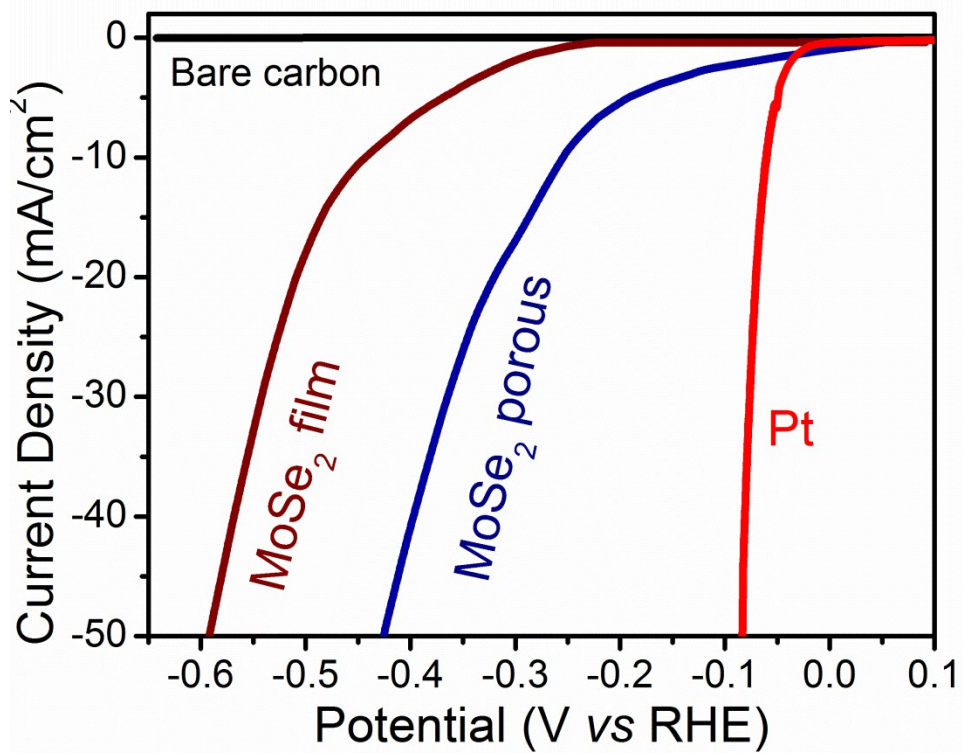


Figure S5 LSV polarization curves for bare carbon electrodes, 0.04 M MoSe₂ film, porous MoSe₂ and Pt in N₂-purged 0.5 M H₂SO₄ solution. Scan rate: 1 mV s⁻¹.